

## Research Article

## Copper Corrosion Inhibition by Cefuroxime Drug in 1M Nitric Acid

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The copper corrosion inhibition in one molar nitric acid by cefuroxime drug is studied through weight loss and quantum chemical methods based on DFT (B3LYP/6-31G (d, p)). The results show that the studied drug is a good inhibitor which adsorbs spontaneously on copper via Langmuir modified isotherm. The thermodynamic adsorption and activation parameters indicate a predominant physisorption process and an endothermic dissolution process. Quantum chemical calculations at B3LYP level with 6-31G (d, p) basis set lead to molecular descriptors such as  $E_{\text{HOMO}}$  (energy of the highest occupied molecular orbital),  $E_{\text{LUMO}}$  (energy of the lowest unoccupied molecular orbital),  $\Delta E$  (energy gap) and  $\mu$  (dipole moment). The global reactivity descriptors such as  $\chi$  (electronegativity),  $\eta$  (hardness),  $S$  (softness) and  $\omega$  (electrophilicity index) were derived using Koopman's theorem and analyzed.

The local reactivity parameters, including Fukui functions  $f(\vec{r})$  and local softness  $s(\vec{r})$  were determined and discussed. Experimental and theoretical results were found to be in good agreement.

**Keywords:** Copper corrosion inhibition, cefuroxime, weight loss, adsorption, DFT, Fukui functions

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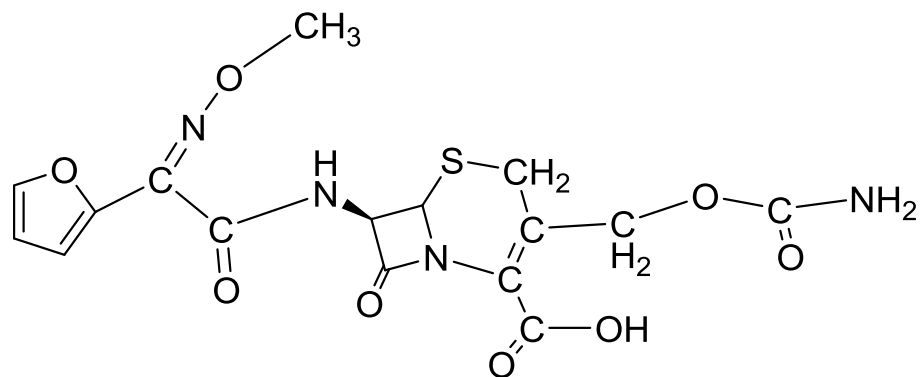
**Introduction**

The environmental, economical and safety consequences of metals corrosion are enormous and their chemical protection has been deeply investigated [1]. Copper and its alloys [2] are often used in many applications in modern chemistry. Copper is a relatively noble metal, however, it undergoes corrosion when being in contact with acidic solutions, especially in the presence of oxygen or other oxidants [3]. Several research methods on inhibition of its corrosion have been reported and it has been established that the use of inhibitors is one of the best methods for the prevention of the corrosion of copper in acidic medium [4]. Organic compounds, which can donate electrons to unoccupied d orbital of the metal surface to form coordinate covalent bonds, and can also accept free electrons from the metal surface by using their anti-bonding orbital to form feedback bonds, constitute excellent corrosion inhibitors [5]. A number of heterocyclic compounds containing nitrogen, oxygen, and sulfur either in the aromatic or long chain carbon system have been reported to be effective inhibitors [6, 7].

Recently, several studies have been carried out on the inhibition of corrosion of metals by drugs due to environmental constraints [8, 9]. Cefuroxime (**Scheme 1**) is the commercial name of (6R, 7R) -3 - {[aminocarbonyl] oxy] methyl} -7 - {[ (2Z) -2- (furan-2-yl) -2- (methoxyimino) acetyl] amino} -8-oxo acid -5-thia-1-azabicyclo [4.2.0] oct-2-ene-2-carboxylic acid, an antibiotic drug which is easily available, environmentally friendly and nontoxic. In view of these favorable characteristic properties, Cefuroxime drug was chosen for the corrosion studies. In order to support experimental studies, quantum chemistry calculations are used to study reaction mechanisms and to interpret the experimental results. To get insight into chemical reactivity and selectivity of organic compounds, authors use DFT parameters including global parameters such as electronegativity  $\chi$  [10], hardness  $\eta$  [11], softness  $S$ , electrophilicity index  $\omega$  [12] and local parameters as condensed Fukui functions  $f(\vec{r})$  [13] and condensed local softness  $s(\vec{r})$  [14]. The aim of the present paper is to evaluate the inhibitive properties of cefuroxime drug against copper corrosion in 1 M  $\text{HNO}_3$ , by analyzing both experimental data and theoretical parameters.

**Experimental****Copper specimen**

The samples of copper used in this study were in the form of rods with 10 mm as length and 2.2 mm as diameter which were cut in commercial copper of purity 95%.



**Scheme 1** Chemical structure of cefuroxime

### Reagents

Cefuroxime of analytical grade with  $C_{16}H_{16}N_4O_8S$  as formula and acetone of purity 99.5% were purchased from Sigma-Aldrich Chemicals. Commercial nitric acid of purity 65% was purchased from Pan Reac AppliChem.

### Solution preparation

1M  $HNO_3$  solutions without or with different concentrations of Cefuroxime ranging from 0.05 to 5 mM were then prepared.

### Weight loss method

Before each measurement, the copper samples were mechanically abraded with different grade emery papers (1/0, 2/0, 3/0, 4/0, 5/0, and 6/0). The specimens were washed thoroughly with double distilled water, degreased and rinsed with acetone and dried in a moisture-free desiccator. Weight loss measurements conducted in a beaker of 100 mL capacity containing 50 mL of the test solution. The immersion time for weight loss was 1h at a given temperature. In order to get good reproducible data, parallel triplicate experiments were performed accurately and the average weight loss was used to calculate the corrosion rate ( $W$ ), the degree of surface coverage ( $\Theta$ ) and the inhibition efficiency (IE) using Equation 1-3 respectively:

$$W = \frac{m_1 - m_2}{St} \quad (1)$$

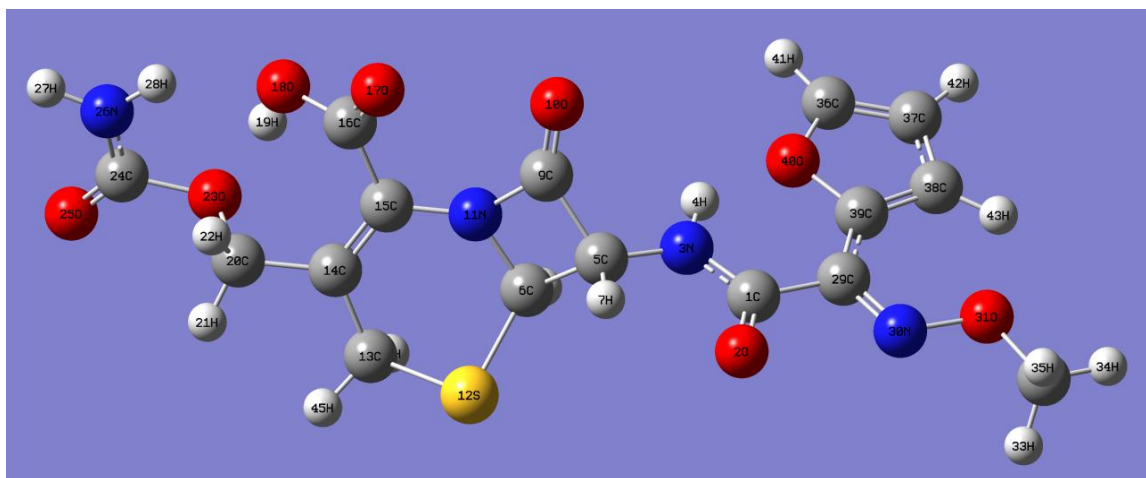
$$\theta = \frac{W_0 - W}{W_0} \quad (2)$$

$$IE(\%) = \left( \frac{W_0 - W}{W_0} \right) * 100 \quad (3)$$

where  $W_0$  and  $W$  are the corrosion rate without and with inhibitor respectively,  $m_1$  and  $m_2$  are the weight before and after immersion in the corrosive aqueous solution respectively,  $S$  is the total surface of the aluminum specimen and  $t$  is the immersion time.

### Quantum Chemical Calculations

The quantum chemical calculations have been performed with Gaussian-09 series of program package [15]. In our calculation we have used Becke's three parameter exchange functional [16] along with the Lee-Yang-Parr nonlocal correlation functional (B3LYP) [17] using 6-31G (d, p) basis set. Quantum chemical methods also have been proved to be a very powerful tool for studying inhibition of corrosion of the metals [18]. Density functional theory (DFT) has been quite successful in providing theoretical basis for popular qualitative chemical concepts like energy of highest occupied molecular orbital ( $E_{HOMO}$ ) and the lowest unoccupied molecular orbital ( $E_{LUMO}$ ), energy gap ( $\Delta E$ ), total electronic energy ( $E$ ) of the molecule through global reactivity parameters such as chemical hardness ( $\eta$ ), global softness ( $S$ ), fraction of electrons transferred ( $\Delta N$ ), electrophilicity index ( $\omega$ ) and local ones such as Fukui function ( $f(\vec{r})$ ) and local softness ( $s(\vec{r})$ ).



**Figure 1** Optimized structure of cefuroxime by B3LYP/6-31G (d, p)

For N-electrons system with total energy E, the electronegativity is given by Equation 4:

$$\chi = -\mu_P = -\left(\frac{\partial E}{\partial N}\right)_{v(\vec{r})} \quad (4)$$

Where  $\mu_P$  and  $v(\vec{r})$  are the chemical and external potentials respectively. The chemical hardness  $\eta$  which is defined as the second derivative of E with respect to N is then given by Equation 5:

$$\eta = \left(\frac{\partial^2 E}{\partial N^2}\right)_{v(\vec{r})} \quad (5)$$

The global softness S is the inverse of the global hardness as seen in Equation 6:

$$S = \frac{1}{\eta} \quad (6)$$

According to Koopman's theorem [19], the ionization potential  $I$  can be approximated as the negative of the highest occupied molecular orbital (HOMO) energy:

$$I = -E_{HOMO} \quad (7)$$

The negative of the lowest unoccupied molecular orbital (LUMO) energy is related to the electron affinity  $A$ :

$$A = -E_{LUMO} \quad (8)$$

The electronegativity was obtained using the ionization energy  $I$  and the electron affinity  $A$  as given in Equation 9:

$$\chi = \frac{I+A}{2} \quad (9)$$

The hardness which is the reciprocal of the electronegativity was obtained by Equation 10:

$$\eta = \frac{I-A}{2} \quad (10)$$

When the organic molecule is in contact with the metal, electrons flow from the system with lower electronegativity to that of higher electronegativity until the chemical potential becomes equal. The fraction of electrons transferred,  $\Delta N$ , was estimated according to Pearson [20]:

$$\Delta N = \frac{\chi_{Cu} - \chi_{inh}}{2(\eta_{Cu} + \eta_{inh})} \quad (11)$$

In this study, we used theoretical values of  $\chi_{Cu}$  and  $\eta_{Cu}$  ( $\eta_{Cu} = 4.98$  eV [12] and  $\eta_{Cu} = 0$  [21]). The global electrophilicity index, introduced by Parr [12] is given by Equation (12):

$$\omega = \frac{\chi^2}{2\eta} \quad (12)$$

The local selectivity of a corrosion inhibitor [22] is generally assessed using Fukui functions. Their values are used to identify which atoms in the inhibitor are more prone to undergo an electrophilic or nucleophilic attack. The change in electron density [23] is the nucleophilic and electrophilic Fukui functions, which are defined as:

$$f(\vec{r}) = \left( \frac{\partial \rho(\vec{r})}{\partial N} \right)_{v(\vec{r})} \quad (13)$$

where  $N$  and  $\rho(\vec{r})$  are the number of electrons and the electron density at position  $\vec{r}$  of the chemical species respectively. After taking care of the discontinuities in  $f(\vec{r})$  versus  $N$  plot, the “condensed-to-atom” approximations of  $f(\vec{r})$ , when multiplied by global softness ( $S$ ) [24] provide local softness values given by Equation 14-15 respectively:

$$s_k^+(\vec{r}) = [q_k(N+1) - q_k(N)]S = f_k^+ S \quad (14)$$

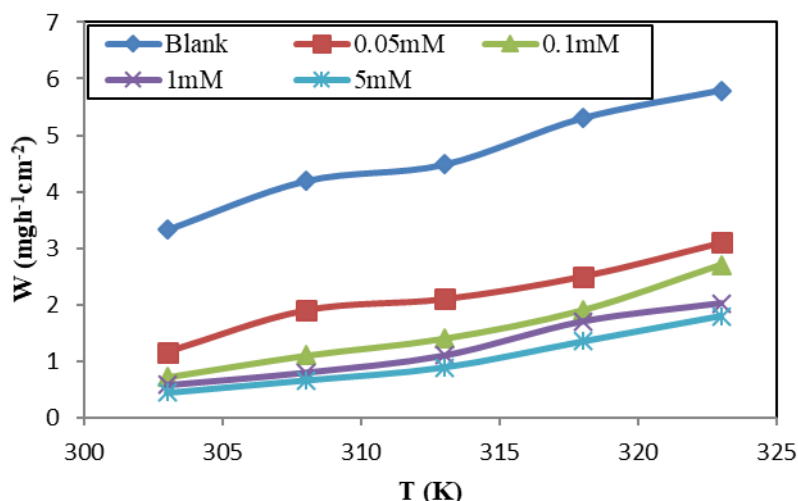
$$s_k^-(\vec{r}) = [q_k(N) - q_k(N-1)]S = f_k^- S \quad (15)$$

In these equations  $q_k(N+1)$ ,  $q_k(N)$  and  $q_k(N-1)$  represent the condensed electronic populations on atom “k” for anionic, neutral and cationic systems respectively. Therefore,  $s_k^+(\vec{r})$  and  $s_k^-(\vec{r})$  represent the condensed local softness values of atom “k” towards nucleophilic and electrophilic attacks.

## Results and discussion

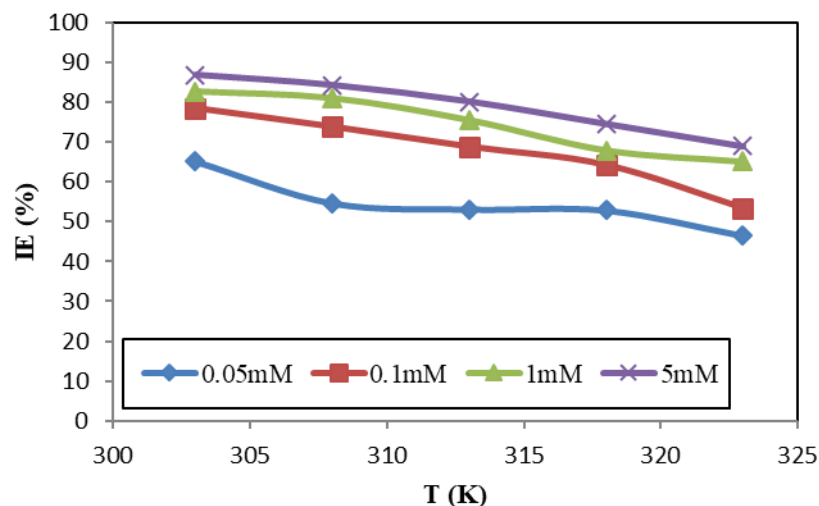
### Effect of concentration and temperature

The corrosion rate curves of copper without and with the addition of cefuroxime in 1M HNO<sub>3</sub> at different temperatures are presented in **Figure 2**. These curves show that corrosion rate of copper in the studied medium, increases with increasing temperature. But this evolution is moderated when the concentration of the studied inhibitor increases, revealing the effectiveness of the molecule as a corrosion inhibitor for copper in 1 M HNO<sub>3</sub>. These results could be interpreted as the formation of a film barrier which isolates the metal from its aggressive environment.



**Figure 2** Evolution of corrosion rate with temperature for different concentrations of cefuroxime

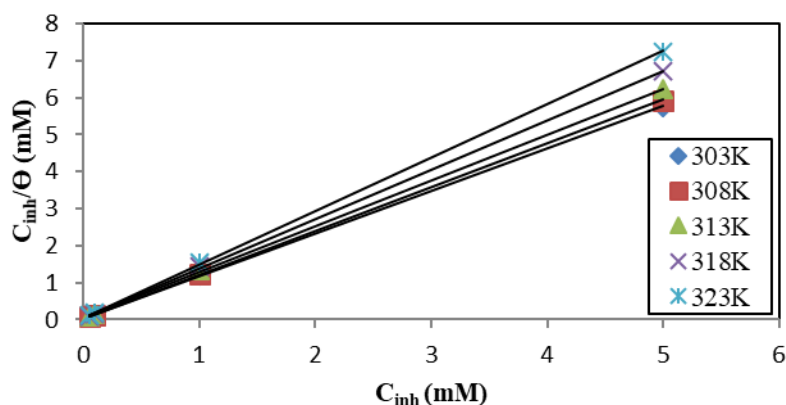
As shown in **Figure 3**, the inhibition efficiency decreases with the rise in temperature for the concentration range studied. It has been reported [25] that the decrease in inhibition efficiency with increase in temperature indicates that the process of adsorption of the inhibitor on the corroding metal surface is physical adsorption.



**Figure 3** Inhibition efficiency versus temperature for different concentrations of cefuroxime

### Adsorption isotherms

The adsorption isotherms study gives knowledge about the interaction of inhibitors on the metal surface. The adsorption isotherms tested in this work are the models of Langmuir, Temkin and Flory-Huggins. By fitting the degree of surface coverage ( $\Theta$ ) and the inhibitor concentration ( $C_{inh}$ ) (**Figure 4**), the best adsorption isotherm obtained graphically is Langmuir adsorption isotherm with the mean value of  $R^2 = 0.999$ .



**Figure 4** Langmuir adsorption isotherm for cefuroxime on copper surface in 1M HNO<sub>3</sub>

The slopes of the straight lines are different from unity, what suggests [26] interactions between adsorbed species on copper surface as well as changes in the values of Gibbs energy with increasing surface coverage. The results reveal a slight deviation from ideal conditions (all the adsorption sites are equivalent) assumed in the Langmuir adsorption model. Therefore, a modified Langmuir equation [27] must be considered. This equation, which takes into account the deviation from the ideal conditions, is given through Equation 16:

$$\frac{C_{inh}}{\theta} = \frac{n}{K_{ads}} + nC_{inh} \quad (16)$$

where  $n$  is the slope of the straight line corresponding to the Langmuir isotherm (see  $n$  values in **Table 1**). The values of adsorption equilibrium constant  $K_{ads}$  were obtained from the intercepts of the straight lines on the  $C_{inh}/\theta$ -axis.  $K_{ads}$  is related [28] to the standard free adsorption energy  $\Delta G_{ads}^0$  according to Equation 17:

$$\Delta G_{ads}^0 = -RT \ln(55.5K_{ads}) \quad (17)$$

where 55.5 is the concentration of water in the solution in mol.L<sup>-1</sup>,  $R$  is the perfect gas constant and  $T$  is the absolute temperature. The calculated values of  $\Delta G_{ads}^0$  are summarized in **Table 2**.

**Table 1** Regression parameters of Langmuir isotherm

T(K)	Correlation coefficient	Slope	Intercept
303	0.9999	1.1475	0.0298
308	1	1.1810	0.0337
313	0.9999	1.2408	0.0434
318	0.9998	1.3341	0.0495
323	0.9999	1.4416	0.0552

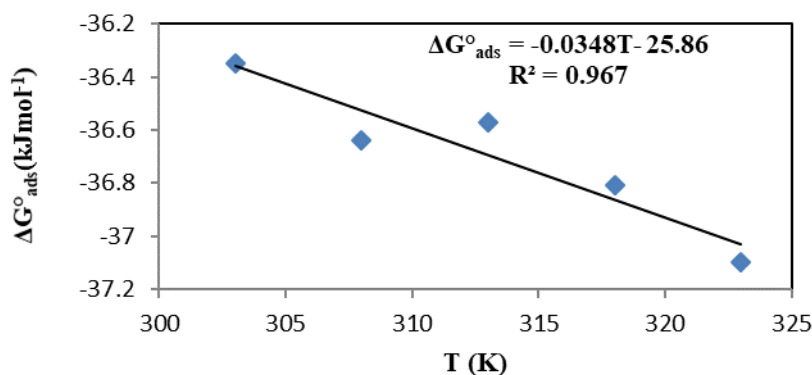
**Table 2** Thermodynamic parameters for the adsorption of cefuroxime on copper surface at different temperatures

T(K)	$K_{ads}(M^{-1})$	$\Delta G_{ads}^0(kJ mol^{-1})$	$\Delta H_{ads}^0(kJ mol^{-1})$	$\Delta S_{ads}^0(J mol^{-1}K^{-1})$
303	33557.05	-36.35		
308	29673.59	-36.64		
313	23041.47	-36.57	-25.899	34.70
318	20202.02	-36.81		
323	18115.94	-37.1		

Generally, values of  $\Delta G_{ads}^0$  around  $-20 kJ mol^{-1}$  are consistent in proving spontaneous adsorption at the interface with electrostatic interactions between the charged molecules and the charged metal (physical adsorption) whereas those more negative than  $-40 kJ mol^{-1}$  involves charge sharing or transfer from the inhibitor's molecule to the metal surface leading to the formation of a donor-acceptor bond (chemical adsorption) [29, 30]. In the present study, the values of  $\Delta G_{ads}^0$  are within the range of  $-37.10$  to  $-36.35 kJ mol^{-1}$  indicating both chemisorptions and physisorption. The change in standard adsorption enthalpy  $\Delta H_{ads}^0$  and the change in standard adsorption entropy  $\Delta S_{ads}^0$  are calculated using Equation 18:

$$\Delta G_{ads}^0 = \Delta H_{ads}^0 - T\Delta S_{ads}^0 \quad (18)$$

The plot of  $\Delta G_{ads}^0$  versus T (**Figure 5**) leads to the determination of  $\Delta H_{ads}^0$  and  $\Delta S_{ads}^0$  as regression parameters with  $\Delta H_{ads}^0$  as the intercept and  $\Delta S_{ads}^0$  as the negative of the slope of the straight line obtained.

**Figure 5**  $\Delta G_{ads}^0$  versus  $T$  for the adsorption of cefuroxime on copper in 1M  $HNO_3$ 

In this study,  $\Delta H_{ads}^0$  is negative, showing an exothermic process. The literature [31] stated that an exothermic process means either physisorption or chemisorptions. Therefore this result confirms that the process of adsorption is both physisorption and chemisorption. The change in adsorption entropy ( $\Delta S_{ads}^0$ ) is positive, meaning that disorder increases during the adsorption process. This situation can be explained by desorption of water molecules replaced by the inhibitor.

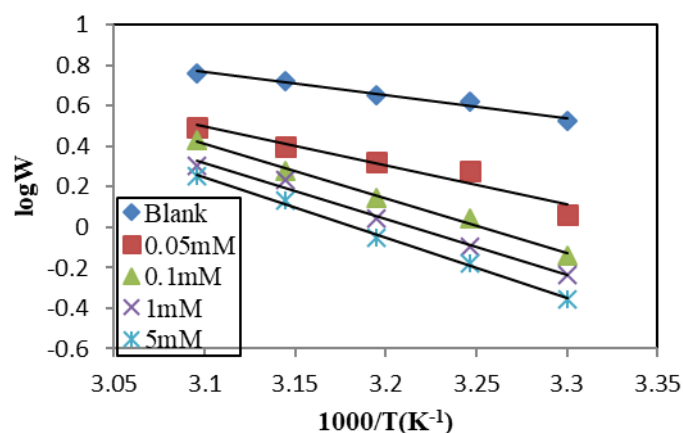
### Effect of temperature

The effect of temperature on the corrosion of copper in  $HNO_3$  containing various concentrations of cefuroxime was investigated using the Arrhenius law (Equation 19):

$$\log W = \log A - \frac{E_a}{2.303RT} \quad (19)$$



where  $E_a$  is the apparent activation energy,  $T$  is the absolute temperature,  $A$  is the preexponential factor. The linear regression plot of  $\log W$  versus  $1/T$  (**Figure 6**) has  $(-\frac{E_a}{2.303R})$  as slope.

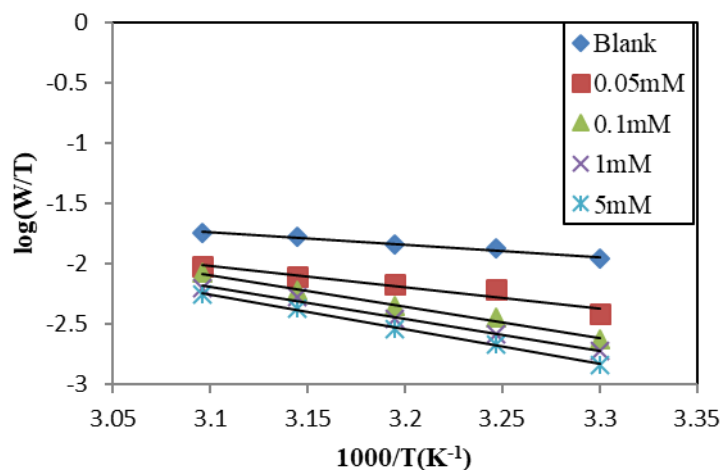


**Figure 6** Arrhenius plots for Copper corrosion in 1M HNO<sub>3</sub> solutions without and with cefuroxime

The effect of the temperature on the corrosion process can also be investigated by determining the change in activation enthalpy  $\Delta H_a^*$  and the change in activation entropy  $\Delta S_a^*$  using the transition state equation (Equation 20):

$$\log\left(\frac{W}{T}\right) = \left[\log\left(\frac{R}{Nh}\right) + \frac{\Delta S_a^*}{2.303R}\right] - \frac{\Delta H_a^*}{2.303RT} \quad (20)$$

where  $h$  is the Planck's constant and  $N$  is the Avogadro number. The transition state plots of  $(W/T)$  versus  $(1/T)$  are given in **Figure 7**. The transition plots were used to determine  $\Delta S_a^*$  and  $\Delta H_a^*$  from respectively the intercepts  $[\log(\frac{R}{Nh}) + \frac{\Delta S_a^*}{2.303R}]$  and the slopes  $(-\frac{\Delta H_a^*}{2.303RT})$ . The obtained values are displayed in **Table 3**.



**Figure 7** Transition state plots for copper corrosion in 1M HNO<sub>3</sub> with or without cefuroxime

It is clear from Table 3 that  $E_a$  in the inhibited solutions are higher than that obtained for the blank, indicating that the corrosion reaction of copper is inhibited by the studied compound [32], hence supports the phenomenon of physical adsorption [33]. Higher values of  $E_a$  in the presence of inhibitor can be correlated with increasing thickness of the double layer which enhances the  $E_a$  of the corrosion process [34]. It is also an indication of a strong inhibitive action of cefuroxime drug by increasing energy barrier for the corrosion process, emphasizing the electrostatic character of the inhibitor's adsorption on the copper surface (physisorption) [35]. The positive sign of change in activation enthalpy reveals an endothermic dissolution process and therefore a slow dissolution of copper [36] in the presence of the studied drug. The change in activation entropy is negative and it increases when the inhibitor

concentration increases, probably due to desorption of the adsorbed species. Similar observation has been reported [37] in the literature.

**Table 3** Activation parameters for copper corrosion without and with cefuroxime in 1M HNO<sub>3</sub>

	$E_a$ (kJmol <sup>-1</sup> )	$\Delta H_a^*$ (kJmol <sup>-1</sup> )	$\Delta S_a^*$ (Jmol <sup>-1</sup> K <sup>-1</sup> )
Blank	21.87	19.24	-170.86
0.05mM	36.57	33.93	-130.53
0.1mM	51.91	49.25	-84.61
1mM	52.90	50.23	-83.41
5mM	57.50	54.83	-70.43

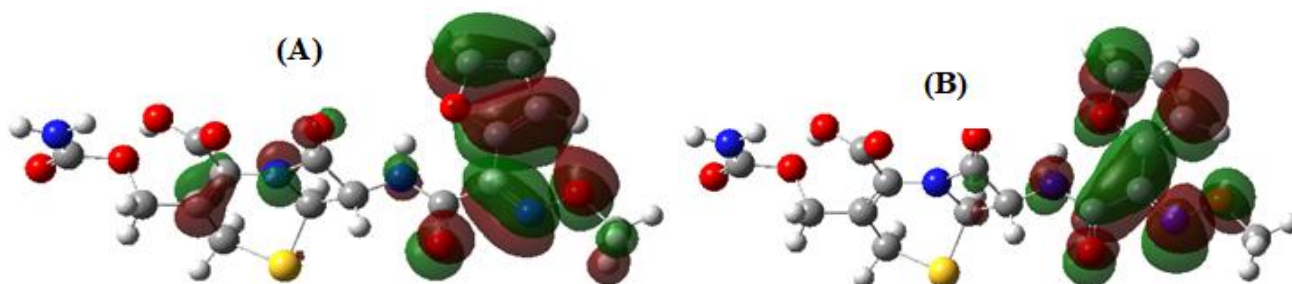
### Quantum chemical calculations

#### Global reactivity

The calculated molecular descriptors are displayed in **Table 4**. From Table 4, it is obvious that the high inhibition efficiency value of cefuroxime can be explained by its high value of  $E_{\text{HOMO}}$  (-6.4841 eV) when considering the values reported in the literature [38-40]. This high value indicates the tendency to donate electrons to empty molecular orbital of copper ions ( $\text{Cu}^{2+}$ :  $[\text{Ar}] 3d^9$ ) [41]. The inhibitor does not only donate electron to the unoccupied d orbital of the metal ion but can also accept electron from the d orbital of the metal leading to the formation of a feed-back bond [42]. The low value of  $E_{\text{LUMO}}$  (-1.9359 eV) compared to that reported in the literature [38, 43] indicates its ability to accept electrons. The energy gap, ( $\Delta E = E_{\text{LUMO}} - E_{\text{HOMO}}$ ) is an important parameter as a function of reactivity of the inhibitor molecule towards the adsorption on the metallic surface. As  $\Delta E$  decreases, the reactivity of the molecule increases leading to increase in the inhibition efficiency of the molecule. Lower values of the energy difference will render good inhibition efficiency, because the energy to remove an electron from the last occupied orbital will be low [44]. In our case, the low value of energy gap ( $\Delta E = 4.5482$  eV) could explain the high inhibition efficiency value ( $\text{IE} (\%) = 88.79$  for  $C_{\text{inh}} = 5$  mM at  $T = 303$  K). The density HOMO and LUMO diagrams are shown in **Figure 8**.

**Table 4** Values of some molecular descriptors

Descriptor	Value	Descriptor	Value
$E_{\text{HOMO}}$ (eV)	-6.4841	I (eV)	6.4841
$E_{\text{LUMO}}$ (eV)	-1.9359	A (eV)	1.9359
$\Delta E$ (eV)	4.5482	$\mu$ (Debye)	4.9152
$\Delta N$	0.1693	$\eta$ (eV)	2.2741
$S$ (eV) <sup>-1</sup>	0.4397	$\omega\mu$	3.8969
$\chi$ (eV)	4.2100	TE (a.u)	-1828.3297



**Figure 8** HOMO (A) and LUMO (B) by B3LYP 6-31G (d, p)

As presented in Figure 8A&B, the density HOMO is distributed almost throughout the molecule whereas the density LUMO is distributed only from the five-membered ring to the antibiotic function.

According to the literature [45], the obtained value of the dipole moment (4.9152D) is high implying the compound's effectiveness as corrosion inhibitor. Ionization energy is a fundamental descriptor of the chemical reactivity of molecules that deals with their stability or their inertness. High ionization energies [46] indicate a high stability of the system while low values denote high reactivity. In our case, the low ionization energy (6.4841 eV) of the molecule could explain its high inhibition efficiency.

Absolute hardness and softness also measure molecular stability and reactivity. The chemical hardness fundamentally signifies the resistance towards the deformation or polarization of electron cloud of a system under a



small perturbation of the chemical reaction. A hard molecule has a large energy gap and a soft molecule a small energy gap [47]. In the present work, Cefuroxime has a small hardness value (2.2741 eV) and a high value of softness ( $(0.4397 \text{ eV})^{-1}$ ) compared with many molecules in the literature. These results confirm those obtained with the earlier mentioned descriptors.

The number ( $\Delta N$ ) of electrons transferred was also calculated and the obtained value (0.1693) shows according to the literature [48] that the inhibition efficiency results from electrons donation.

The absolute electrophilicity index was also calculated. According to the definition, this index measures the propensity of chemical species to accept electrons. A high value of electrophilicity index [12] describes a good electrophile while a small value of electrophilicity index denotes a good nucleophile. This reactivity index measures the stabilization in energy when the system acquires an additional electronic charge from the environment. The obtained value ( $\omega = 3.8969$ ) shows that the inhibitor is an electrophile molecule: it can receive electrons.

### Local reactivity

Fukui functions compute local reactivity indices that makes possible to rationalize the reactivity of individual molecular orbital contributions. The condensed Fukui function and local softness indices allow one distinguish each part of the molecule on the basis of its distinct chemical behavior due to the different substituted functional group. The preferred site for nucleophilic attack is the atom in the molecule where the value of  $f_k^+$  is maximum and it is associated with the LUMO energy while the site for electrophilic attack is controlled by the values of  $f_k^-$  which is associated with the HOMO energy. The local softness contains the information similar to those condensed Fukui function plus additional information about the total molecular softness. A high value of  $s_k^+$  indicates high nucleophilicity and the high value of  $s_k^-$  indicates high electrophilicity. The Fukui and softness indices values for Cefuroxime drug calculated with B3LYP/6-31G (d, p) are displayed in **Table 5**.

**Table 5** Charges of some selected atoms, condensed Fukui functions and local softness indices

Atom	$q_k(N+1)$	$q_k(N)$	$q_k(N-1)$	$f_k^+$	$f_k^-$	$s_k^+$	$s_k^-$
1C	0.745	0.739	0.747	0.006	-0.008	0.003	-0.004
2O	-0.505	-0.492	-0.465	-0.013	-0.027	-0.006	-0.012
3N	-0.748	-0.759	-0.760	0.011	0.001	0.005	0.000
5C	-0.157	-0.142	-0.112	-0.015	-0.030	-0.007	-0.013
<b>6C</b>	<b>-0.233</b>	<b>-0.215</b>	<b>-0.274</b>	<b>-0.018</b>	<b>0.059</b>	<b>-0.008</b>	<b>0.026</b>
9C	0.682	0.698	0.682	-0.016	0.016	-0.007	0.007
10O	-0.464	-0.429	-0.359	-0.035	-0.070	-0.015	-0.031
11N	-0.698	-0.754	-0.675	0.056	-0.079	0.025	-0.035
12S	-0.381	0.321	0.426	-0.702	-0.105	-0.309	-0.046
<b>13C</b>	<b>-0.353</b>	<b>-0.657</b>	<b>-0.646</b>	<b>0.304</b>	<b>-0.011</b>	<b>0.134</b>	<b>-0.005</b>
14C	-0.091	0.019	0.040	-0.110	-0.021	-0.048	-0.009
15C	0.240	0.277	0.310	-0.037	-0.033	-0.016	-0.015
16C	0.619	0.662	0.706	-0.043	-0.044	-0.019	-0.019
17O	-0.484	-0.439	-0.423	-0.045	-0.016	-0.020	-0.007
18O	-0.575	-0.608	-0.580	0.033	-0.028	0.015	-0.012
20C	-0.191	-0.242	-0.230	0.051	-0.012	0.022	-0.005
23O	-0.521	-0.493	-0.504	-0.028	0.011	-0.012	0.005
24C	0.835	0.809	0.974	0.026	-0.165	0.011	-0.073
25O	-0.544	-0.463	-0.550	-0.081	0.087	-0.036	0.038
26N	-0.795	-0.771	-0.761	-0.024	-0.010	-0.011	-0.004
29C	0.149	0.149	0.148	0.000	0.001	0.000	0.000
30N	-0.279	-0.270	-0.238	-0.009	-0.032	-0.004	-0.014
31O	-0.378	-0.369	-0.347	-0.009	-0.022	-0.004	-0.010
32C	-0.297	-0.307	-0.326	0.010	0.019	0.004	0.008
36C	0.108	0.107	0.124	0.001	-0.017	0.000	-0.007
37C	-0.266	-0.260	-0.246	-0.006	-0.014	-0.003	-0.006
38C	-0.177	-0.169	-0.150	-0.008	-0.019	-0.004	-0.008
39C	0.325	0.326	0.342	-0.001	-0.016	0.000	-0.007
40O	-0.525	-0.536	-0.537	0.011	0.001	0.005	0.000

The analysis of **Table 5** shows that according to the Fukui theory of reactivity, C (13) is the nucleophilic attacks center when C (6) is the electrophilic attacks center.

## Conclusion

The following conclusions can be drawn from this study:

- Inhibition efficiency is temperature and concentration dependent;
- Cefuroxime drug adsorbs on copper surface according to modified Langmuir adsorption isotherm;
- Adsorption thermodynamic functions and activation parameters indicate a spontaneous adsorption process and predominant physisorption;
- Global reactivity parameters explain the good inhibition efficiency of cefuroxime;
- Fukui functions and local softness indices show the nucleophilic and electrophilic attacks sites in the molecule.

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